

Masaharu Shiratani

List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

301
papers

4,267
citations

34
h-index

51
g-index

342
ext. papers

4,936
ext. citations

2.4
avg, IF

5.6
L-index

#	Paper	IF	Citations
301	Nanostructured Ge and GeSn films by high-pressure He plasma sputtering for high-capacity Li ion battery anodes.. <i>Scientific Reports</i> , 2022 , 12, 1742	4.9	2
300	Improved luminescence performance of Yb ³⁺ -Er ³⁺ -Zn ²⁺ : Y ₂ O ₃ phosphor and its application to solar cells. <i>Optical Materials</i> , 2022 , 123, 111928	3.3	0
299	Outcomes of Pulsed Electric Fields and Nonthermal Plasma Treatments on Seed Germination and Protein Functions. <i>Agronomy</i> , 2022 , 12, 482	3.6	0
298	Impact of surface morphologies of substrates on the epitaxial growth of magnetron-sputtered (ZnO) x (InN) _{1-x} films. <i>Japanese Journal of Applied Physics</i> , 2021 , 60, SAAB02	1.4	1
297	Time of Flight Size Control of Carbon Nanoparticles Using Ar+CH ₄ Multi-Hollow Discharge Plasma Chemical Vapor Deposition Method. <i>Processes</i> , 2021 , 9, 2	2.9	1
296	Impact of atmospheric pressure plasma treated seeds on germination, morphology, gene expression and biochemical responses. <i>Japanese Journal of Applied Physics</i> , 2021 , 60, 040502	1.4	8
295	Highly efficient and transparent counter electrode for application in bifacial solar cells. <i>Chemical Physics Letters</i> , 2021 , 768, 138369	2.5	5
294	Comparison between Ar+CH ₄ cathode and anode coupling chemical vapor depositions of hydrogenated amorphous carbon films. <i>Thin Solid Films</i> , 2021 , 729, 138701	2.2	1
293	Synthesis of Yb ³⁺ /Ho ³⁺ co-doped Y ₂ O ₃ nanoparticles and its application to dye sensitized solar cells. <i>Journal of Molecular Structure</i> , 2021 , 1228, 129479	3.4	4
292	Long-term response of Norway spruce to seed treatment with cold plasma: Dependence of the effects on the genotype. <i>Plasma Processes and Polymers</i> , 2021 , 18, 2000159	3.4	3
291	Impact of seed color and storage time on the radish seed germination and sprout growth in plasma agriculture. <i>Scientific Reports</i> , 2021 , 11, 2539	4.9	12
290	Possible impact of plasma oxidation on the structure of the C-terminal domain of SARS-CoV-2 spike protein: a computational study. <i>Applied Physics Express</i> , 2021 , 14, 027002	2.4	7
289	Green route for ammonium nitrate synthesis: fertilizer for plant growth enhancement.. <i>RSC Advances</i> , 2021 , 11, 28521-28529	3.7	2
288	Alterations of DNA Methylation Caused by Cold Plasma Treatment Restore Delayed Germination of Heat-Stressed Rice (<i>Oryza sativa</i> L.) Seeds. <i>ACS Agricultural Science and Technology</i> , 2021 , 1, 5-10		8
287	Plasma treatment causes structural modifications in lysozyme, and increases cytotoxicity towards cancer cells. <i>International Journal of Biological Macromolecules</i> , 2021 , 182, 1724-1736	7.9	11
286	Passivating antireflection coating of crystalline silicon using i/n a-Si:H/SiN ₂ trilayer. <i>Journal of Physics and Chemistry of Solids</i> , 2021 , 156, 110127	3.9	2
285	Effects of concentrated light on the performance and stability of a quasi-solid electrolyte in dye-sensitized solar cells. <i>Chemical Physics Letters</i> , 2021 , 781, 138986	2.5	2

284	Cold plasma treatment of <i>Arabidopsis thaliana</i> (L.) seeds modulates plant-associated microbiome composition. <i>Applied Physics Express</i> , 2020 , 13, 076001	2.4	3
283	Growth of single crystalline films on lattice-mismatched substrates through 3D to 2D mode transition. <i>Scientific Reports</i> , 2020 , 10, 4669	4.9	7
282	Characteristics of crystalline sputtered LaFeO thin films as photoelectrochemical water splitting photocathodes. <i>Nanoscale</i> , 2020 , 12, 9653-9660	7.7	7
281	Improved Nanoscale Al-Doped ZnO with a ZnO Buffer Layer Fabricated by Nitrogen-Mediated Crystallization for Flexible Optoelectronic Devices. <i>ACS Applied Nano Materials</i> , 2020 , 3, 2480-2490	5.6	5
280	Impact of radish sprouts seeds coat color on the electron paramagnetic resonance signals after plasma treatment. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, SHHF01	1.4	13
279	Influence of osmolytes and ionic liquids on the Bacteriorhodopsin structure in the absence and presence of oxidative stress: A combined experimental and computational study. <i>International Journal of Biological Macromolecules</i> , 2020 , 148, 657-665	7.9	9
278	Effects of surrounding gas on plasma-induced downward liquid flow. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, SHHF02	1.4	3
277	Plasma Treatment Effect on the Paramagnetic Species of Barley Seed Radical [⊙] Intensity: An EPR Study. <i>Plasma Medicine</i> , 2020 , 10, 159-168	1.1	3
276	Low-stress diamond-like carbon films containing carbon nanoparticles fabricated by combining rf sputtering and plasma chemical vapor deposition. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, 100906	1.4	2
275	Experimental identification of the reactive oxygen species transported into a liquid by plasma irradiation. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, 110502	1.4	5
274	Structural modification of NADPH oxidase activator (Noxa 1) by oxidative stress: An experimental and computational study. <i>International Journal of Biological Macromolecules</i> , 2020 , 163, 2405-2414	7.9	9
273	Effect of hydrogen dilution on the silicon cluster volume fraction of a hydrogenated amorphous silicon film prepared using plasma-enhanced chemical vapor deposition. <i>Current Applied Physics</i> , 2020 , 20, 191-195	2.6	1
272	Relationship between cold plasma treatment-induced changes in radish seed germination and phytohormone balance. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, SH1001	1.4	18
271	Real-time monitoring of surface passivation of crystalline silicon during growth of amorphous and epitaxial silicon layer. <i>Journal of Applied Physics</i> , 2020 , 128, 033302	2.5	3
270	Size and flux of carbon nanoparticles synthesized by Ar+CH ₄ multi-hollow plasma chemical vapor deposition. <i>Diamond and Related Materials</i> , 2020 , 109, 108050	3.5	8
269	Graphene-Si ₃ N ₄ nanocomposite blended polymer counter electrode for low-cost dye-sensitized solar cells. <i>Chemical Physics Letters</i> , 2020 , 758, 137920	2.5	5
268	Plasma Agriculture from Laboratory to Farm: A Review. <i>Processes</i> , 2020 , 8, 1002	2.9	52
267	Cold Plasma Treatment of Sunflower Seeds Modulates Plant-Associated Microbiome and Stimulates Root and Lateral Organ Growth. <i>Frontiers in Plant Science</i> , 2020 , 11, 568924	6.2	11

266	Influence of alkyl chain substitution of ammonium ionic liquids on the activity and stability of tobacco etch virus protease. <i>International Journal of Biological Macromolecules</i> , 2020 , 155, 439-446	7.9	5
265	Local supply of reactive oxygen species into a tissue model by atmospheric-pressure plasma-jet exposure. <i>Journal of Applied Physics</i> , 2019 , 125, 213303	2.5	8
264	Impact of heterointerface properties of crystalline germanium heterojunction solar cells. <i>Thin Solid Films</i> , 2019 , 685, 225-233	2.2	2
263	Effects of nitrogen impurity on ZnO crystal growth on Si substrates. <i>MRS Advances</i> , 2019 , 4, 1557-1563	0.7	
262	Identification and Suppression of Si-H ₂ Bond Formation at P/I Interface in a-Si:H Films Deposited by SiH ₄ Plasma CVD. <i>Plasma and Fusion Research</i> , 2019 , 14, 4406141-4406141	0.5	
261	Effects of Gas Pressure on the Size Distribution and Structure of Carbon Nanoparticles Using Ar + CH ₄ Multi-Hollow Discharged Plasma Chemical Vapor Deposition. <i>Plasma and Fusion Research</i> , 2019 , 14, 4406115-4406115	0.5	4
260	Dielectric barrier discharge plasma treatment-induced changes in sunflower seed germination, phytohormone balance, and seedling growth. <i>Applied Physics Express</i> , 2019 , 12, 126003	2.4	19
259	Visualization Study on Interaction Between Nonequilibrium Atmospheric Pressure He Plasma Jet and Liquid Solution. <i>Journal of Smart Processing</i> , 2019 , 8, 58-63	0.2	
258	Spatial-Structure of Fluctuation of Amount of Nanoparticles in Amplitude-Modulated VHF Discharge Reactive Plasma. <i>Plasma and Fusion Research</i> , 2019 , 14, 4406120-4406120	0.5	0
257	Effect of Higher-Order Silane Deposition on Spatial Profile of Si-H ₂ /Si-H Bond Density Ratio of a-Si:H Films. <i>Plasma and Fusion Research</i> , 2019 , 14, 4406144-4406144	0.5	
256	Sputter Epitaxy of (ZnO) _x (InN) _{1-x} films on Lattice-mismatched Sapphire Substrate. <i>MRS Advances</i> , 2019 , 4, 1551-1556	0.7	1
255	The effect of the H ₂ /(H ₂ + Ar) flow-rate ratio on hydrogenated amorphous carbon films grown using Ar/H ₂ /C ₂ H ₄ plasma chemical vapor deposition. <i>Thin Solid Films</i> , 2018 , 660, 891-898	2.2	3
254	Impact of Gamma rays and DBD plasma treatments on wastewater treatment. <i>Scientific Reports</i> , 2018 , 8, 2926	4.9	27
253	Effects of Gas Velocity on Deposition Rate and Amount of Cluster Incorporation into a-Si:H Films Fabricated by SiH ₄ Plasma Chemical Vapor Deposition. <i>Plasma and Fusion Research</i> , 2018 , 13, 1406082-1406082	0.5	2
252	Progress in photovoltaic performance of organic/inorganic hybrid solar cell based on optimal resistive Si and solvent modified poly(3,4-ethylenedioxythiophene) poly(styrenesulfonate) junction. <i>Progress in Photovoltaics: Research and Applications</i> , 2018 , 26, 145-150	6.8	8
251	Current status and future prospects of agricultural applications using atmospheric-pressure plasma technologies. <i>Plasma Processes and Polymers</i> , 2018 , 15, 1700073	3.4	114
250	Transportation of reactive oxygen species in a tissue phantom after plasma irradiation. <i>Japanese Journal of Applied Physics</i> , 2018 , 57, 01AG01	1.4	4
249	Plasma agriculture: A rapidly emerging field. <i>Plasma Processes and Polymers</i> , 2018 , 15, 1700174	3.4	125

248	Photoluminescence of (ZnO) _{0.82} (InN) _{0.18} Films: Incident Light Angle Dependence. <i>Materials Science Forum</i> , 2018 , 941, 2099-2103	0.4	1
247	Effects of Sputtering Pressure on (ZnO) _x (InN) _{1-x} Crystal Film Growth at 450°C. <i>Materials Science Forum</i> , 2018 , 941, 2093-2098	0.4	
246	Cross-Correlation Analysis of Fluctuations of Interactions between Nanoparticles and Low Pressure Reactive Plasmas. <i>Materials Science Forum</i> , 2018 , 941, 2104-2108	0.4	
245	Morphology Evolution Of ZnO Thin Films Deposited By Nitrogen Mediated Crystallization Method. <i>MATEC Web of Conferences</i> , 2018 , 159, 02031	0.3	3
244	Particle behavior and its contribution to film growth in a remote silane plasma. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 050601	2.9	1
243	Hysteresis in volume fraction of clusters incorporated into a-Si:H films deposited by SiH ₄ plasma chemical vapor deposition. <i>Surface and Coatings Technology</i> , 2017 , 326, 388-394	4.4	5
242	Densities and Surface Reaction Probabilities of Oxygen and Nitrogen Atoms During Sputter Deposition of ZnInON on ZnO. <i>IEEE Transactions on Plasma Science</i> , 2017 , 45, 323-327	1.3	6
241	Enhanced light harvesting and charge recombination control with TiO ₂ /PbCdS/CdS based quantum dot-sensitized solar cells. <i>Journal of Electroanalytical Chemistry</i> , 2017 , 788, 131-136	4.1	18
240	Plant Growth Enhancement of Seeds Immersed in Plasma Activated Water. <i>MRS Advances</i> , 2017 , 2, 995-1000	10.0	25
239	Low temperature rapid formation of Au-induced crystalline Ge films using sputtering deposition. <i>Thin Solid Films</i> , 2017 , 641, 59-64	2.2	4
238	Effects of sputtering gas pressure dependence of surface morphology of ZnO films fabricated via nitrogen mediated crystallization. <i>MRS Advances</i> , 2017 , 2, 265-270	0.7	4
237	Blue Photoluminescence of (ZnO) _{0.92} (InN) _{0.08} . <i>MRS Advances</i> , 2017 , 2, 277-282	0.7	5
236	The protective action of osmolytes on the deleterious effects of gamma rays and atmospheric pressure plasma on protein conformational changes. <i>Scientific Reports</i> , 2017 , 7, 8698	4.9	15
235	Impact of an ionic liquid on protein thermodynamics in the presence of cold atmospheric plasma and gamma rays. <i>Physical Chemistry Chemical Physics</i> , 2017 , 19, 25277-25288	3.6	13
234	Performance enhancement of quantum dot-sensitized solar cells based on polymer nano-composite catalyst. <i>Electrochimica Acta</i> , 2017 , 249, 337-342	6.7	2
233	Biogenic reductive preparation of magnetic inverse spinel iron oxide nanoparticles for the adsorption removal of heavy metals. <i>Chemical Engineering Journal</i> , 2017 , 307, 74-84	14.7	179
232	Variation in structure of proteins by adjusting reactive oxygen and nitrogen species generated from dielectric barrier discharge jet. <i>Scientific Reports</i> , 2016 , 6, 35883	4.9	32
231	Mechanism and comparison of needle-type non-thermal direct and indirect atmospheric pressure plasma jets on the degradation of dyes. <i>Scientific Reports</i> , 2016 , 6, 34419	4.9	49

230	Cellulose: A Smart Material for Water Purification 2016 , 335-346		2
229	Production of In, Au, and Pt nanoparticles by discharge plasmas in water for assessment of their bio-compatibility and toxicity. <i>MRS Advances</i> , 2016 , 1, 1301-1306	0.7	
228	Plant Growth Response to Atmospheric Air Plasma Treatments of Seeds of 5 Plant Species. <i>MRS Advances</i> , 2016 , 1, 1265-1269	0.7	6
227	Surface Modification of Polymer Counter Electrode for Low Cost Dye-sensitized Solar Cells. <i>Electrochimica Acta</i> , 2016 , 210, 880-887	6.7	11
226	Catalytic Improvement on Counter Electrode of Dye-Sensitized Solar Cells Using Electrospun Pt Nano-Fibers. <i>Journal of Nanoscience and Nanotechnology</i> , 2016 , 16, 3332-7	1.3	1
225	Effects of plasma irradiation using various feeding gases on growth of <i>Raphanus sativus</i> L. <i>Archives of Biochemistry and Biophysics</i> , 2016 , 605, 129-40	4.1	44
224	Improvement of Charge Transportation in Si Quantum Dot-Sensitized Solar Cells Using Vanadium Doped TiO ₂ . <i>Journal of Nanoscience and Nanotechnology</i> , 2016 , 16, 4875-9	1.3	3
223	Effects of gas flow rate on deposition rate and number of Si clusters incorporated into a-Si:H films. <i>Japanese Journal of Applied Physics</i> , 2016 , 55, 01AA19	1.4	4
222	Reduced recombination with an optimized barrier layer on TiO ₂ in PbS/CdS core shell quantum dot sensitized solar cells. <i>New Journal of Chemistry</i> , 2016 , 40, 3423-3431	3.6	21
221	Simple method of improving harvest by nonthermal air plasma irradiation of seeds of <i>Arabidopsis thaliana</i> (L.). <i>Applied Physics Express</i> , 2016 , 9, 016201	2.4	57
220	Polymer counter electrode of poly(3,4-ethylenedioxythiophene):Poly(4-styrenesulfonate) containing TiO ₂ nano-particles for dye-sensitized solar cells. <i>Journal of Power Sources</i> , 2016 , 307, 25-30	8.9	29
219	Effects of deposition rate and ion bombardment on properties of a-C:H films deposited by H-assisted plasma CVD method. <i>Japanese Journal of Applied Physics</i> , 2016 , 55, 01AA11	1.4	7
218	DNA Microarray Analysis of Plant Seeds Irradiated by Active Oxygen Species in Oxygen Plasma. <i>Plasma Medicine</i> , 2016 , 6, 459-471	1.1	11
217	Effect of sulfur doped TiO ₂ on photovoltaic properties of dye-sensitized solar cells. <i>Electronic Materials Letters</i> , 2016 , 12, 530-536	2.9	8
216	Correlation between SiH ₂ /SiH and light-induced degradation of p ⁺ i hydrogenated amorphous silicon solar cells. <i>Japanese Journal of Applied Physics</i> , 2016 , 55, 07LE03	1.4	7
215	Effects of nonthermal plasma jet irradiation on the selective production of H ₂ O ₂ and NO ₂ in liquid water. <i>Journal of Applied Physics</i> , 2016 , 120, 203302	2.5	43
214	Fluctuation of Position and Energy of a Fine Particle in Plasma Nanofabrication. <i>Materials Science Forum</i> , 2016 , 879, 1772-1777	0.4	4
213	Two-dimensional concentration distribution of reactive oxygen species transported through a tissue phantom by atmospheric-pressure plasma-jet irradiation. <i>Applied Physics Express</i> , 2016 , 9, 076202	2.4	37

212	Effects of irradiation distance on supply of reactive oxygen species to the bottom of a Petri dish filled with liquid by an atmospheric O ₂ /He plasma jet. <i>Journal of Applied Physics</i> , 2016 , 119, 173301	2.5	26
211	Low temperature synthesis of silicon quantum dots with plasma chemistry control in dual frequency non-thermal plasmas. <i>Physical Chemistry Chemical Physics</i> , 2016 , 18, 15697-710	3.6	14
210	Room Temperature Fabrication of (ZnO) _x (InN) _{1-x} films with Step-Terrace Structure by RF Magnetron Sputtering. <i>MRS Advances</i> , 2016 , 1, 115-119	0.7	5
209	Improving the performance of quantum dot sensitized solar cells through CdNiS quantum dots with reduced recombination and enhanced electron lifetime. <i>Dalton Transactions</i> , 2016 , 45, 8447-57	4.3	38
208	Optical Bandgap Energy of Si Nanoparticle Composite Films Deposited by a Multi-Hollow Discharge Plasma Chemical Vapor Deposition Method. <i>Journal of Nanoscience and Nanotechnology</i> , 2016 , 16, 10753-10757	1.3	7
207	Effects of cluster incorporation into hydrogenated amorphous silicon films in initial discharge phase on film stability. <i>Thin Solid Films</i> , 2015 , 587, 126-131	2.2	8
206	Multigeneration Effects of Plasma Irradiation to Seeds of Arabidopsis Thaliana and Zinnia on Their Growth. <i>Materials Research Society Symposia Proceedings</i> , 2015 , 1723, 7		7
205	Photovoltaic application of Si nanoparticles fabricated by multihollow plasma discharge CVD: Dye and Si co-sensitized solar cells. <i>Japanese Journal of Applied Physics</i> , 2015 , 54, 01AD02	1.4	4
204	Structural alternation of tandem dye-sensitized solar cells based on mesh-type of counter electrode. <i>Electrochimica Acta</i> , 2015 , 179, 206-210	6.7	4
203	Gas Flow Rate Dependence of the Discharge Characteristics of a Plasma Jet Impinging Onto the Liquid Surface. <i>IEEE Transactions on Plasma Science</i> , 2015 , 43, 4081-4087	1.3	9
202	Fabrication of p-i-n solar cells utilizing ZnInON by RF magnetron sputtering. <i>Materials Research Society Symposia Proceedings</i> , 2015 , 1741, 53		2
201	Antioxidative activity and growth regulation of Brassicaceae induced by oxygen radical irradiation. <i>Japanese Journal of Applied Physics</i> , 2015 , 54, 06GD01	1.4	34
200	Effects of gas flow on oxidation reaction in liquid induced by He/O ₂ plasma-jet irradiation. <i>Journal of Applied Physics</i> , 2015 , 118, 043301	2.5	33
199	Influence of ionic liquid and ionic salt on protein against the reactive species generated using dielectric barrier discharge plasma. <i>Scientific Reports</i> , 2015 , 5, 17781	4.9	49
198	Deposition of Germanium Crystalline Nanoparticle Composite Films by Using Reactive Dusty Plasma Process and their Application for Quantum-Dot Solar Cells. <i>Journal of Smart Processing</i> , 2015 , 4, 6-11	0.2	
197	Effects of Atmospheric Air Plasma Irradiation to Seeds of Radish Sprouts on Chlorophyll and Carotenoids Concentrations in their Leaves. <i>Materials Research Society Symposia Proceedings</i> , 2015 , 1723, 34		2
196	Effects of morphology of buffer layers on ZnO/sapphire heteroepitaxial growth by RF magnetron sputtering. <i>Materials Research Society Symposia Proceedings</i> , 2015 , 1741, 33		3
195	Comparative Study on the Pulmonary Toxicity of Indium Hydroxide, Indium-Tin Oxide, and Indium Oxide Following Intratracheal Instillations into the Lungs of Rats. <i>Materials Research Society Symposia Proceedings</i> , 2015 , 1723, 19		

194	Fabrication of ZnInON/ZnO multi-quantum well solar cells. <i>Thin Solid Films</i> , 2015 , 587, 106-111	2.2	11
193	Real-time mass measurement of dust particles deposited on vessel wall in a divertor simulator using quartz crystal microbalances. <i>Journal of Nuclear Materials</i> , 2015 , 463, 865-868	3.3	0
192	Analysis on the photovoltaic property of Si quantum dot-sensitized solar cells. <i>International Journal of Precision Engineering and Manufacturing</i> , 2014 , 15, 339-343	1.7	5
191	Effects of Atmospheric Air Plasma Irradiation on pH of Water 2014 ,		1
190	Dust Hour Glass in a Capacitive RF Discharge. <i>IEEE Transactions on Plasma Science</i> , 2014 , 42, 2672-2673	1.3	1
189	Visualization of the Distribution of Oxidizing Substances in an Atmospheric Pressure Plasma Jet. <i>IEEE Transactions on Plasma Science</i> , 2014 , 42, 2482-2483	1.3	24
188	Theory for correlation between plasma fluctuation and fluctuation of nanoparticle growth in reactive plasmas. <i>Japanese Journal of Applied Physics</i> , 2014 , 53, 010201	1.4	8
187	The enhancement of dye adsorption in dye-sensitized solar module by an electrical adsorption method. <i>Thin Solid Films</i> , 2014 , 554, 118-121	2.2	6
186	Performance enhancement of dye and Si quantum dot hybrid nanostructured solar cell with TiO ₂ barrier. <i>Transactions of the Materials Research Society of Japan</i> , 2014 , 39, 321-324	0.2	
185	Growth mechanism of ZnO deposited by nitrogen mediated crystallization. <i>Materials Research Express</i> , 2014 , 1, 036403	1.7	3
184	Self-organized formation of hierarchically-ordered structures in laser-activated plasma CVD of sp ³ -bonded BN films. <i>Japanese Journal of Applied Physics</i> , 2014 , 53, 010202	1.4	1
183	Formation of microcones accompanied with ripple patterns in laser-activated plasma CVD of sp ³ -bonded BN films. <i>Journal of Materials Research</i> , 2014 , 29, 485-491	2.5	
182	Sterilization characteristics of the surfaces of agricultural products using active oxygen species generated by atmospheric plasma and UV light. <i>Japanese Journal of Applied Physics</i> , 2014 , 53, 05FR03	1.4	19
181	Off-axis sputter deposition of ZnO films on c-sapphire substrates by utilizing nitrogen-mediated crystallization method. <i>Optical Engineering</i> , 2014 , 53, 087109	1.1	8
180	Nanostructure Control of Si and Ge Quantum Dots Based Solar Cells Using Plasma Processes. <i>Materials Science Forum</i> , 2014 , 783-786, 2022-2027	0.4	1
179	Performance dependence of Si quantum dot-sensitized solar cells on counter electrode. <i>Japanese Journal of Applied Physics</i> , 2014 , 53, 05FZ01	1.4	3
178	SiC Nanoparticle Composite Anode for Li-Ion Batteries. <i>Materials Research Society Symposia Proceedings</i> , 2014 , 1678, 7		3
177	Electrochemical impedance analysis on the additional layers for the enhancement on the performance of dye-sensitized solar cell. <i>Thin Solid Films</i> , 2014 , 554, 122-126	2.2	6

176	Plasma induced long-term growth enhancement of <i>Raphanus sativus</i> L. using combinatorial atmospheric air dielectric barrier discharge plasmas. <i>Current Applied Physics</i> , 2014 , 14, S149-S153	2.6	64
175	Mass density control of carbon films deposited by H-assisted plasma CVD method. <i>Surface and Coatings Technology</i> , 2013 , 228, S15-S18	4.4	8
174	Transport control of dust particles via the electrical asymmetry effect: experiment, simulation and modelling. <i>Journal Physics D: Applied Physics</i> , 2013 , 46, 245202	3	15
173	Growth control of ZnO nano-rod with various seeds and photovoltaic application. <i>Journal of Physics: Conference Series</i> , 2013 , 441, 012029	0.3	
172	Analysis on the effect of polysulfide electrolyte composition for higher performance of Si quantum dot-sensitized solar cells. <i>Electrochimica Acta</i> , 2013 , 95, 43-47	6.7	29
171	Characteristics of photocurrent generation in the near-ultraviolet region in Si quantum-dot sensitized solar cells. <i>Thin Solid Films</i> , 2013 , 544, 93-98	2.2	10
170	The improvement on the performance of quantum dot-sensitized solar cells with functionalized Si. <i>Thin Solid Films</i> , 2013 , 546, 284-288	2.2	6
169	Effects of nanoparticle incorporation on properties of microcrystalline films deposited using multi-hollow discharge plasma CVD. <i>Surface and Coatings Technology</i> , 2013 , 228, S550-S553	4.4	1
168	Discharge power dependence of carbon dust flux in a divertor simulator. <i>Journal of Nuclear Materials</i> , 2013 , 438, S788-S791	3.3	4
167	The reduction of charge recombination and performance enhancement by the surface modification of Si quantum dot-sensitized solar cell. <i>Electrochimica Acta</i> , 2013 , 87, 213-217	6.7	18
166	Effects of DC substrate bias voltage on dust flux in the Large Helical Device. <i>Journal of Nuclear Materials</i> , 2013 , 438, S727-S730	3.3	3
165	Dust particle formation due to interaction between graphite and helicon deuterium plasmas. <i>Fusion Engineering and Design</i> , 2013 , 88, 28-32	1.7	9
164	Plasma interactions with aminoacid (l-alanine) as a basis of fundamental processes in plasma medicine. <i>Current Applied Physics</i> , 2013 , 13, S59-S63	2.6	14
163	High Amount Cluster Incorporation in Initial Si Film Deposition by SiH ₄ Plasma Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 01AD01	1.4	8
162	H ₂ /N ₂ Plasma Etching Rate of Carbon Films Deposited by H-Assisted Plasma Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 01AB01	1.4	2
161	Correlation between Volume Fraction of Silicon Clusters in Amorphous Silicon Films and Optical Emission Properties of Si* and SiH*. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 11NA07	1.4	3
160	Improvement of Si Adhesion and Reduction of Electron Recombination for Si Quantum Dot-Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 01AD05	1.4	9
159	Flux Control of Carbon Nanoparticles Generated due to Interactions between Hydrogen Plasmas and Graphite Using DC-Biased Substrates. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 11NA08	1.4	1

158	Characteristics of Crystalline Silicon/Si Quantum Dot/Poly(3,4-ethylenedioxythiophene) Hybrid Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 11NA05	1.4	1
157	Effects of Nitrogen on Crystal Growth of Sputter-Deposited ZnO Films for Transparent Conducting Oxide. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 11NB03	1.4	11
156	Improvement on the Electron Transfer of Dye-Sensitized Solar Cell Using Vanadium Doped TiO ₂ . <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 11NM02	1.4	11
155	Epitaxial Growth of ZnInON Films with Tunable Band Gap from 1.7 to 3.3 eV on ZnO Templates. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 11NM06	1.4	11
154	Study on the Fabrication of Paint-Type Si Quantum Dot-Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 10MB07	1.4	7
153	Effects of Hydrogen Dilution on ZnO Thin Films Fabricated via Nitrogen-Mediated Crystallization. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 01AC08	1.4	9
152	Investigations on Plasma-Biomolecules Interactions as Fundamental Process for Plasma Medicine. <i>Journal of Physics: Conference Series</i> , 2013 , 441, 012001	0.3	5
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